(.)	,) 2	
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L Number	Hits	Search Text	DB	- Time et
3	6	(((((mask\$3 or resist\$3 or photoresist)	USPAT;	- Time stamp
		same ((etch\$3 or chemical\$2 adj mil\$3 or	US-PGPUB;	2003/10/13 21:13
		deoxidiz\$3 or anodiz\$3) and metal)) and	EPO; JPO;	
		(mask\$3 or resist\$3 or photoresist) same	IBM TDB	1
		(aluminum or "Al" or steel or titanium or	1011_100	
		"Ti")) and (mask\$3 or resist\$3 or		
		photoresist) same (\$4urethane adj3		
•		\$4acrylate or \$4urethane adj3 \$4acrylate))		
		and (mask\$3 or resist\$3 or photoresist)		
		same (peel\$4 or pull\$4 or remov\$4 or		
		lift\$3 adj off)) and (mask\$3 or resist\$3	1	
	1	or photoresist) same (scrib\$4 or cut\$4 or		
		mark\$4 or scrap\$4)		
4	25		USPAT;	2003/10/13 21:14
		((deoxidiz\$3 or anodiz\$3) and metal)) and	US-PGPUB;	
		(peel\$4 or remov\$4 or scrib\$4 or pull\$4 or	EPO; JPO;	
		lift\$3 adj off or cut\$4 or scrap\$4) near3	IBM TDB	
		(mask\$3 or resist\$3 or photoresist) same	_	
c	_	(seal\$3)		
5	1		USPAT;	2003/10/13 21:18
		same ((deoxidiz\$3 or anodiz\$3) and metal)	US-PGPUB;	
			EPO; JPO;	
6	0	/magkant an magka and 1	IBM_TDB	
0	U	, the state of mash, and first and scaret same	USPAT;	2003/10/13 21:18
		((deoxidiz\$3 or anodiz\$3) and metal)	US-PGPUB;	
			EPO; JPO;	
7	95	(216/42,44,47,48,101-102.ccls. or	IBM_TDB	0000 400 400 00
·	,,,	430/320,323-324.ccls. or	USPAT;	2003/10/13 21:20
		205/122,135,153,188,320,324.ccls.) and	US-PGPUB; EPO; JPO;	
		seal\$3 same mask\$3	IBM TDB	
8	170	(IRGACURE adj "1700") or (IRACURE adj	USPAT;	2003/10/13 21:22
		"1700")	US-PGPUB;	2003/10/13 21:22
			EPO; JPO;	
			IBM TDB	
9	29	((IRGACURE adj "1700") or (IRACURE adj	USPAT;	2003/10/13 21:24
		"1700")) and (wax or (synergist and	US-PGPUB;	
1		triethanolamine))	EPO; JPO;	
ŀ			IBM TDB	
-	51785	(mask\$3 or resist\$3 or photoresist) same	USPAT;	2003/06/03 09:04
		((etch\$3 or chemical\$2 adj mil\$3 or	US-PGPUB;	
		deoxidiz\$3 or anodiz\$3) and metal)	EPO; JPO;	
_	25136	//magk\$3 on mastat\$3	IBM_TDB	
	23130	((mask\$3 or resist\$3 or photoresist) same	USPAT;	2003/06/03 09:05
		((etch\$3 or chemical\$2 adj mil\$3 or deoxidiz\$3 or anodiz\$3) and metal)) and	US-PGPUB;	
		(mask\$3 or resist\$3 or photoresist) same	EPO; JPO;	
		(aluminum or "Al" or steel or titanium or	IBM_TDB	
	1	"Ti")	ĺ	
-	26	(((mask\$3 or resist\$3 or photoresist) same	USPAT;	2002/05/20 10:00
1		((etch\$3 or chemical\$2 adj mil\$3 or	US-PGPUB;	2003/05/26 16:28
		deoxidiz\$3 or anodiz\$3) and metal)) and	EPO; JPO;	
-		(mask\$3 or resist\$3 or photoresist) same	IBM TDB	
		(aluminum or "Al" or steel or titanium or		
		"Ti")) and (mask\$3 or resist\$3 or	İ	
		photoresist) same (\$4urethane adi3		
		\$4acrylate or \$4urethane adj3 \$4acrylate)	1	

48		
N)		

	922	((((mask\$3 or resist\$3 or photoresist) same ((etch\$3 or chemical\$2 adj mil\$3 or deoxidiz\$3 or anodiz\$3) and metal)) and (mask\$3 or resist\$3 or photoresist) same (aluminum or "Al" or steel or titanium or "Ti")) and (mask\$3 or resist\$3 or photoresist) same (\$4acrylate or \$4acrylate)) not (((mask\$3 or resist\$3 or photoresist) same ((etch\$3 or chemical\$2 adj mil\$3 or deoxidiz\$3 or anodiz\$3) and metal)) and (mask\$3 or resist\$3 or photoresist) same (aluminum or "Al" or steel or titanium or "Ti")) and (mask\$3 or resist\$3 or photoresist) same (\$4urethane adj3 \$4acrylate or \$4urethane adj3 \$4acrylate))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/05/26 16:27
-	26	<pre>((((mask\$3 or resist\$3 or photoresist) same ((etch\$3 or chemical\$2 adj mil\$3 or deoxidiz\$3 or anodiz\$3) and metal)) and (mask\$3 or resist\$3 or photoresist) same (aluminum or "Al" or steel or titanium or "Ti")) and (mask\$3 or resist\$3 or photoresist) same (\$4urethane adj3 \$4acrylate or \$4urethane adj3 \$4acrylate)) and (mask\$3 or resist\$3 or photoresist) same (peel\$4 or pull\$4 or remov\$4 or lift\$3 adj off)</pre>	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/05/26 16:32
	854	same ((etch\$3 or chemical\$2 adj mil\$3 or deoxidiz\$3 or anodiz\$3) and metal)) and (mask\$3 or resist\$3 or photoresist) same (aluminum or "Al" or steel or titanium or "Ti")) and (mask\$3 or resist\$3 or photoresist) same (\$4acrylate or \$4acrylate)) not ((((mask\$3 or resist\$3 or photoresist) same (etch\$3 or chemical\$2 adj mil\$3 or deoxidiz\$3 or anodiz\$3) and metal)) and (mask\$3 or resist\$3 or photoresist) same (aluminum or "Al" or steel or titanium or "Ti")) and (mask\$3 or resist\$3 or photoresist) same (\$4urethane adj3 \$4acrylate or \$4urethane adj3 \$4acrylate))) and (mask\$3 or resist\$3 or photoresist) same (peel\$4 or pull\$4 or remov\$4 or lift\$3 adj off)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/05/26 16:32
	6	(((((mask\$3 or resist\$3 or photoresist) same ((etch\$3 or chemical\$2 adj mil\$3 or deoxidiz\$3 or anodiz\$3) and metal)) and (mask\$3 or resist\$3 or photoresist) same (aluminum or "Al" or steel or titanium or "Ti")) and (mask\$3 or resist\$3 or photoresist) same (\$4urethane adj3 \$4acrylate or \$4urethane adj3 \$4acrylate) and (mask\$3 or resist\$3 or photoresist) same (peel\$4 or pull\$4 or remov\$4 or lift\$3 adj off)) and (mask\$3 or resist\$3 or photoresist) same (scrib\$4 or cut\$4 or mark\$4 or scrap\$4)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/10/13 21:12
-	1560	<pre>(mask\$3 or resist\$3 or photoresist) same ((deoxidiz\$3 or anodiz\$3) and metal)</pre>	USPAT; US-PGPUB; EPO; JPO; IBM TDB	2003/06/03 09:55
-	308	((mask\$3 or resist\$3 or photoresist) same ((deoxidiz\$3 or anodiz\$3) and metal)) and (peel\$4 or remov\$4 or scrib\$4) adj3 (mask\$3 or resist\$3 or photoresist)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/06/03 09:10
_	495	(peel\$4 or remov\$4 or scrib\$4 or pull\$4 or	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/06/03 09:11

	T 644			
-	511		USPAT;	2003/06/03 09:12
		((deoxidiz\$3 or anodiz\$3) and metal)) and	US-PGPUB;	
		(peel\$4 or remov\$4 or scrib\$4 or pull\$4 or	EPO; JPO;	1
		lift\$3 adj off or cut\$4 or scrap\$4) near3	IBM_TDB	
_	24	(mask\$3 or resist\$3 or photoresist)		
	24		USPAT;	2003/10/13 21:13
		((deoxidiz\$3 or anodiz\$3) and metal)) and	US-PGPUB;	
		(peel\$4 or remov\$4 or scrib\$4 or pull\$4 or lift\$3 adj off or cut\$4 or scrap\$4) near3	EPO; JPO;	
		(mask\$3 or resist\$3 or photoresist) same	IBM_TDB	
		(seal\$3)		
-	1	(maskant or mask) and line adj sealant	IICDAM.	2002/10/10
	_	same ((deoxidiz\$3 or anodiz\$3) and metal)	USPAT;	2003/10/13 21:17
		((dodination of disodizes) and metal)	US-PGPUB; EPO; JPO;	
			IBM TDB	
-	0	(maskant or mask) and line adj sealer same	USPAT;	2003/10/13 21:18
		((deoxidiz\$3 or anodiz\$3) and metal)	US-PGPUB;	2003/10/13 21:18
		,	EPO; JPO;	
			IBM TDB	
_	92	1 (== +, -=,,, 10/101 102 01	USPAT;	2003/10/13 21:18
		430/320,323-324 or	US-PGPUB;	2000, 20, 13 21.10
		205/122,135,153,188,320,324).ccls. and	EPO; JPO;	
		seal\$3 same mask\$3	IBM TDB	
-	145		USPAT;	2003/10/13 21:21
		"1700")	US-PGPUB;	
			EPO; JPO;	
_	23	//TDCACUDE #1700#\	IBM_TDB	
	23		USPAT;	2003/10/13 21:24
		"1700")) and (wax or (synergist and triethanolamine))	US-PGPUB;	
		criethanoramine,,	EPO; JPO;	
-	3	((IRGACURE adj "1700") or (IRACURE adj	IBM_TDB	0000/00/00
		"1700")) and (cur\$3 or expos\$3 or light\$3	USPAT;	2003/10/13 15:54
		or UV or ultraviolet or actinic or	US-PGPUB;	
		radiat\$3) same (\$5watt adj per adj square	EPO; JPO;	
		adj \$5meter or "W/cm.sup.2" or	IBM_TDB	
		"W/m.sup.2")		
1-	762	(mask\$3 or resist\$3 or photoresist) same	USPAT;	2003/10/13 16:13
		(peel\$4 or pull\$4 or remov\$4 or lift\$3 adi	US-PGPUB;	2003/10/13 10.13
		off) and \$4acrylate and (cur\$3 or expos\$3	EPO; JPO;	
		or light\$3 or UV or ultraviolet or actinic	IBM TDB	
		or radiat\$3) same (\$5watt adj per adj	_	
		square adj \$5meter or \$1"W/cm.sup.2" or		
	4.0	\$1"W/m.sup.2")		
-	40	(mask\$3 or resist\$3 or photoresist) same	USPAT;	2003/10/13 16:16
		(peel\$4 or pull\$4 or remov\$4 or lift\$3 adj	US-PGPUB;	
		off) and \$4acrylate.ti,ab. and (cur\$3 or	EPO; JPO;	
	1	expos\$3 or light\$3 or UV or ultraviolet or	IBM_TDB	
		actinic or radiat\$3) same (\$5watt adj per		
<u> </u>		adj square adj \$5meter or \$1"W/cm.sup.2")		

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